Supporting Information

Quasi-Two-Dimensional α-Molybdenum Oxide Thin Film Prepared by Magnetron Sputtering for Neuromorphic Computing

Zhenfa Wu,[a] Peng Shi,[a] Ruofei Xing,[a] Yuzhi Xing,[a] Yufeng Ge,[a] Lin Wei,*[b] Dong Wang,[a] Le Zhao,[c] Shishen Yan[a] and Yanxue Chen*[a]

[a]*School of Physics, and State Key Laboratory of Crystal Materials, Shandong University, Jinan 250100, China*

[b]*School of Microelectronics, Shandong University, Jinan 250100, China*

[c]*School of Electronic and Information Engineering, Qilu University of Technology, Jinan 250353, China*

* *Corresponding author. E-mail: cyx@sdu.edu.cn (Y. X. Chen), wl2003@sdu.edu.cn (L. Wei)*
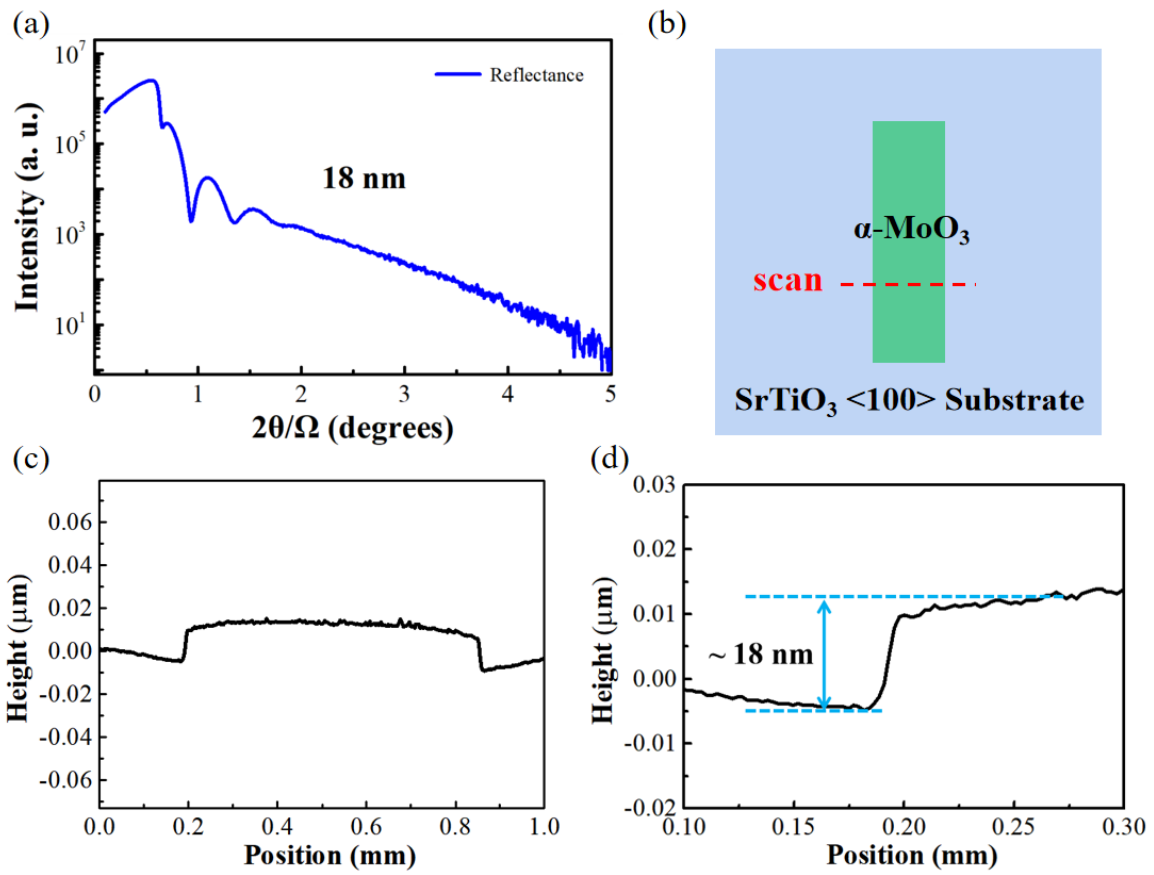
Fig. S1. The thickness characterization of α-MoO₃ thin film. (a) The X-ray reflectance spectrum of α-MoO₃ thin film. (b) Schematic image of the α-MoO₃ bar grown on SrTiO₃ substrate through a hard mask. (c, d) The step profiler spectrum of the α-MoO₃ bar.